
Uniformity studies of scintillator tiles coupled with Surface Mounted SiPM

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CALICE Collab. Meeting, Annecy

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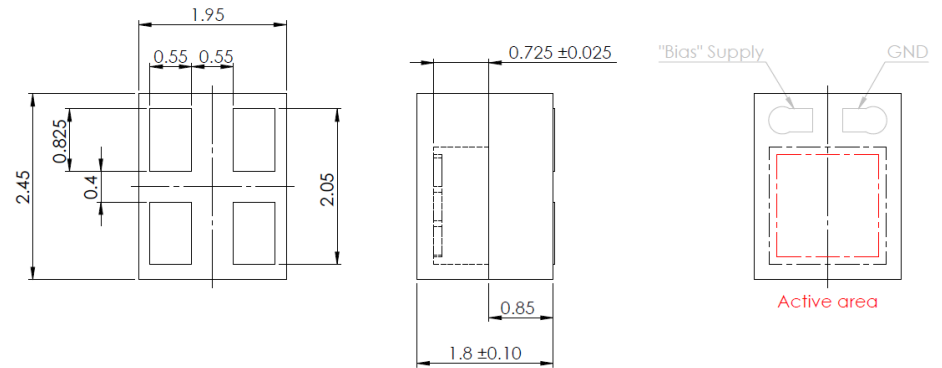
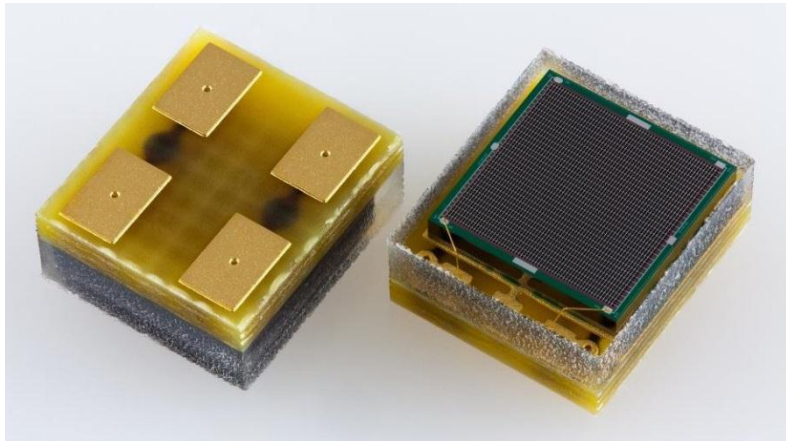
Outline

- Motivations
- Geant4 full simulation studies
- Uniformity measurements at MPI Physik, Munich
- Summary

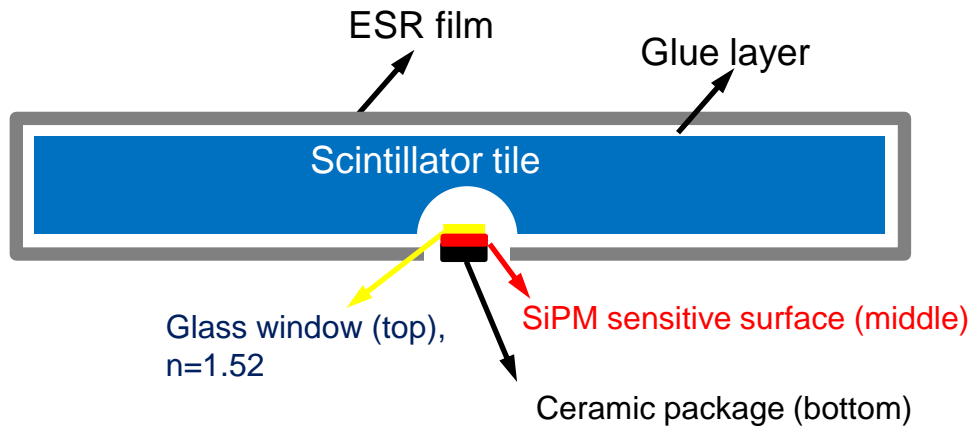
Motivations

- Surface Mounted SiPM
 - No pins: more tolerance for alignment
 - Easier to solder on HBU boards automatically
 - Mass assembly by pick-and-place machine (talk by Phi Chau)

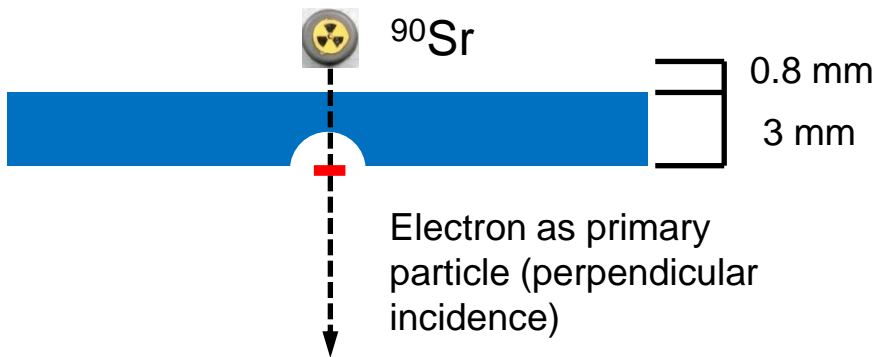
SMD SiPM module (KETEK)



Simulation: setup for uniformity scan

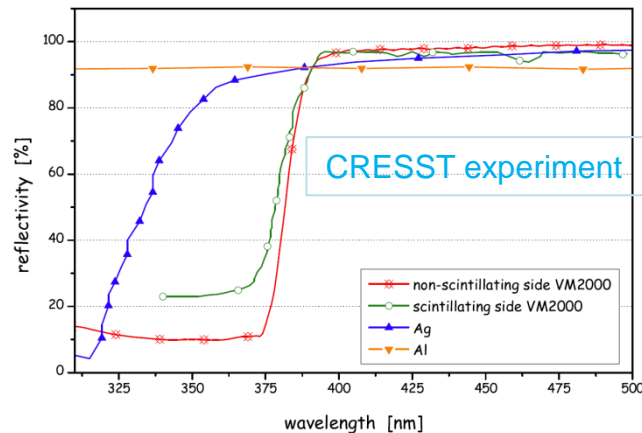


Scintillator tile: 30x30x3 mm³
 KETEK SiPM: 1.2x1.2 mm²
 Geant4 9.6.0.p01
 Optical boundary model:
 polished or ground (UNIFIED Model)



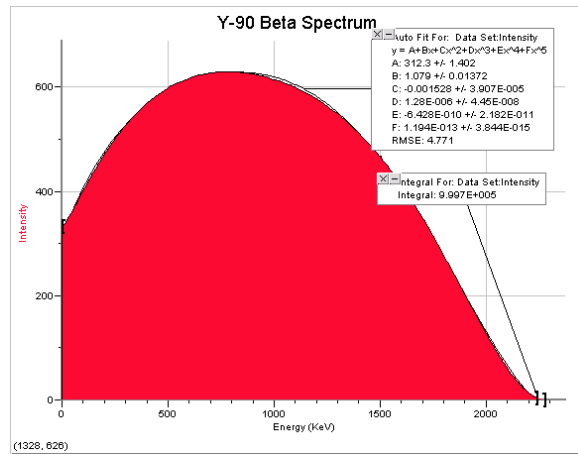
Scan step size: 1 mm
 1 run: simulate 50 events at each position
 30x30 positions to cover the whole tile area

Measured curve:
 ESR reflectivity vs wavelength

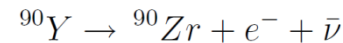
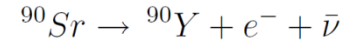


Plot courtesy of
 Frank Simon

Simulation: details

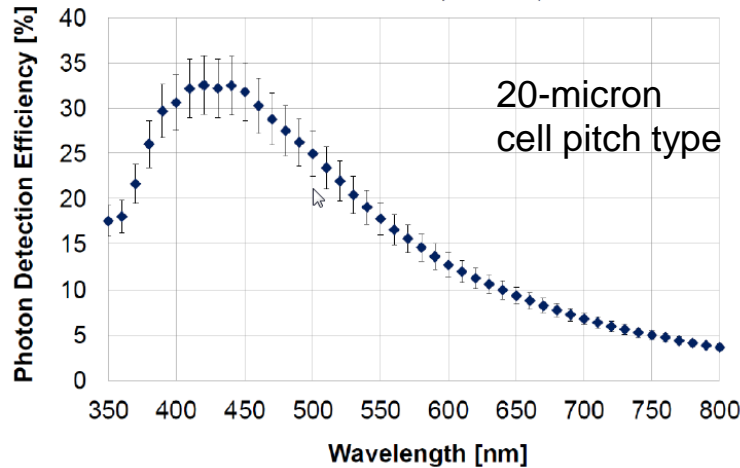


^{90}Sr energy spectrum:
 use normalized polynomial fitting as p.d.f. to sample



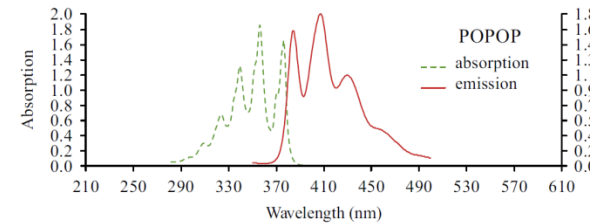
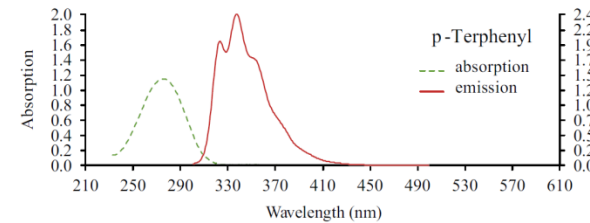
Ref 1: Silicon Strips and Pixel Technologies, Excellence in Detectors and Instrumentation Technologies 2011, CERN

KETEK PDE curve



Ref 2: SiPM Development at KETEK, CALICE Collaboration Meeting, March 2013 Hamburg

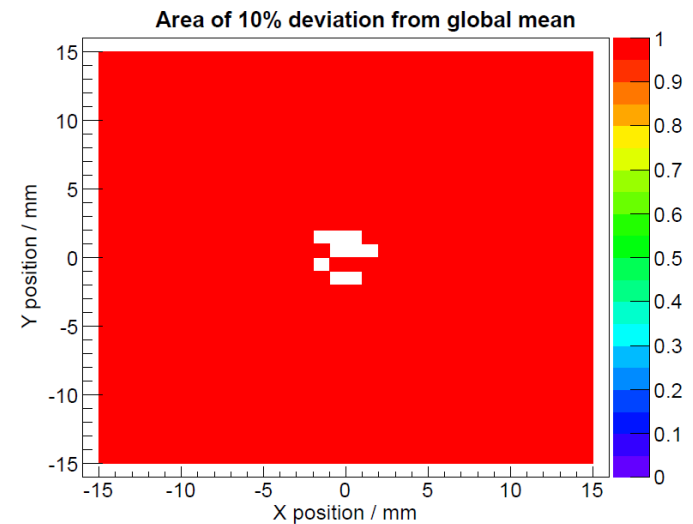
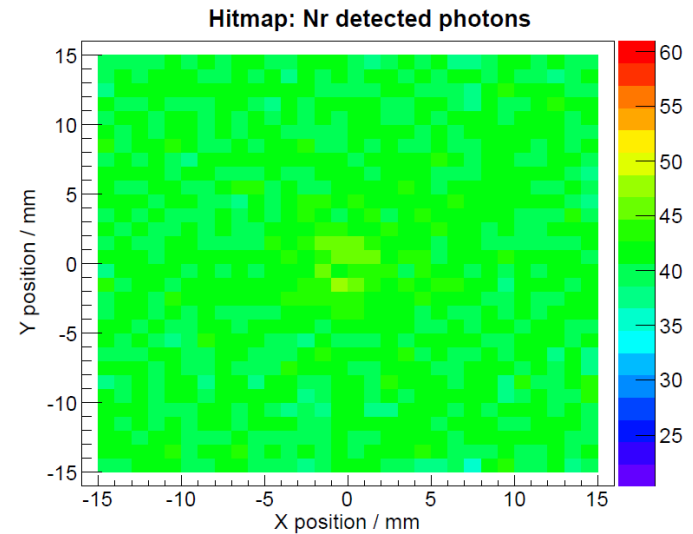
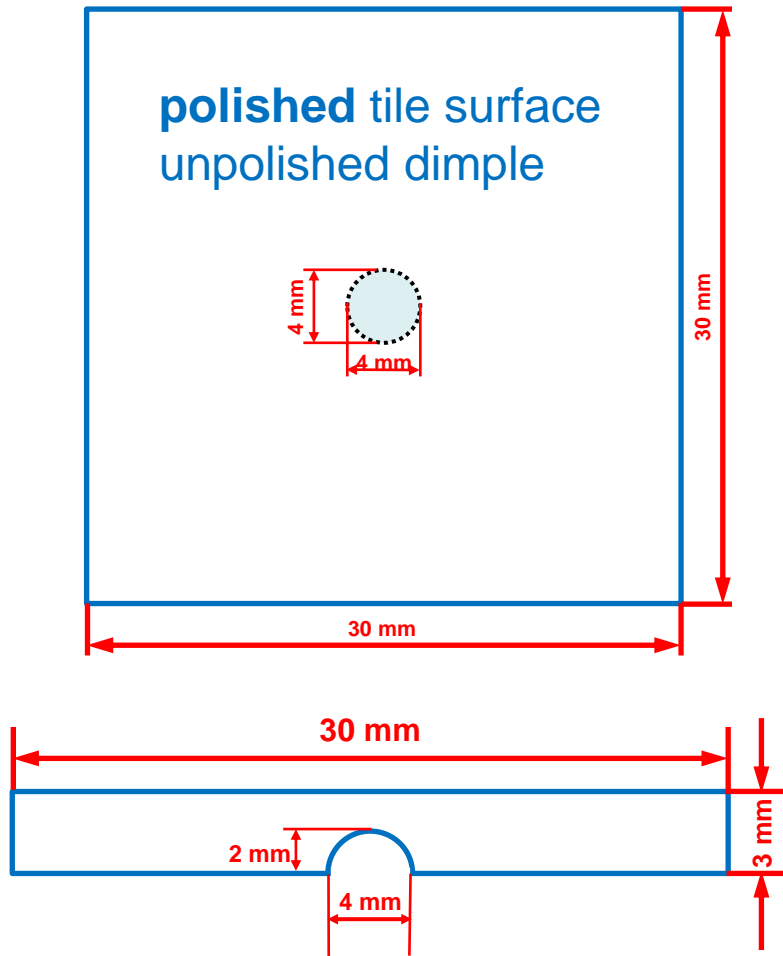
Scintillator emission spectra



Scintillator from NA62, produced by IHEP (Protvino, Russia)

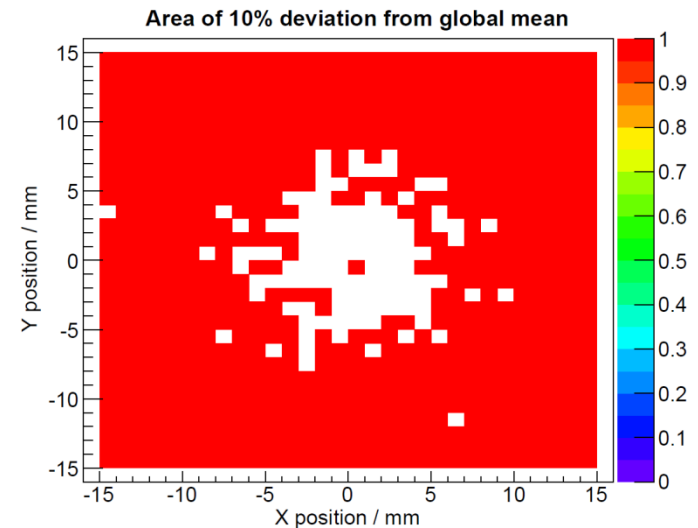
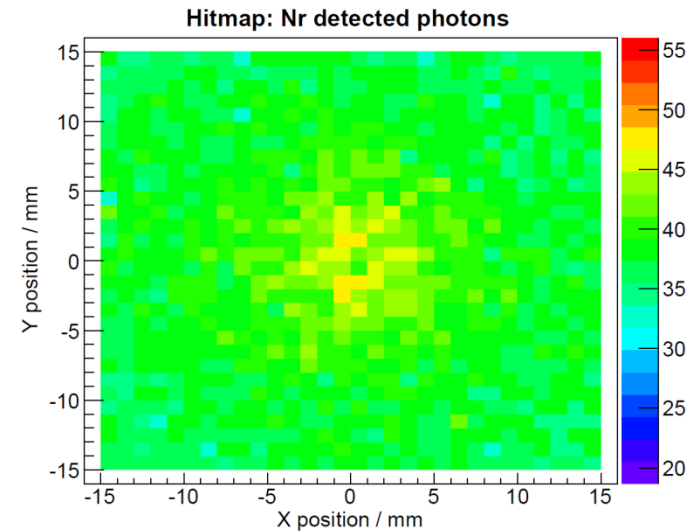
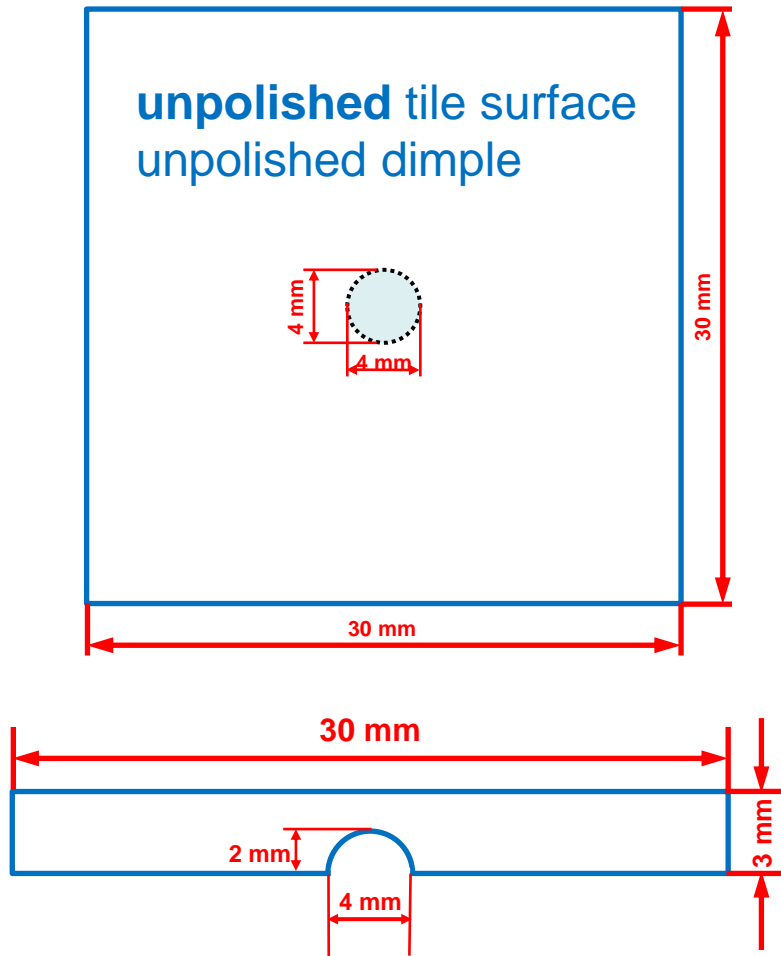
Ref 3: Nuclear Instruments and Methods in Physics Research A 577 (2007) 523

Simulation: hemisphere dimple (1)



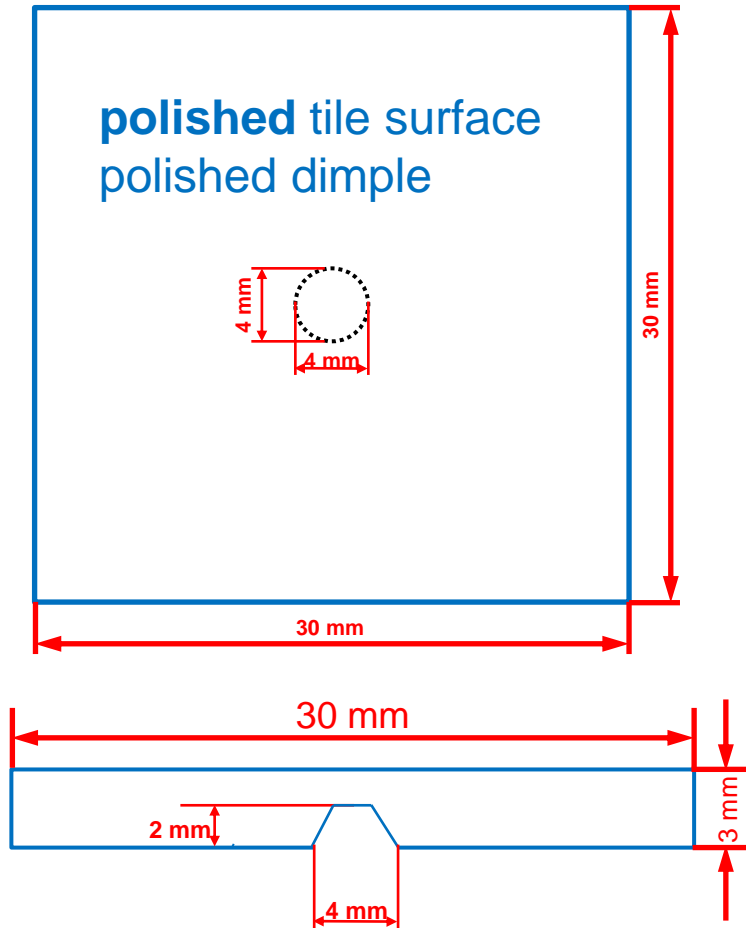
Average: 40.7 detected photons
10% deviation from average: 99.0 % area

Simulation: hemisphere dimple (2)



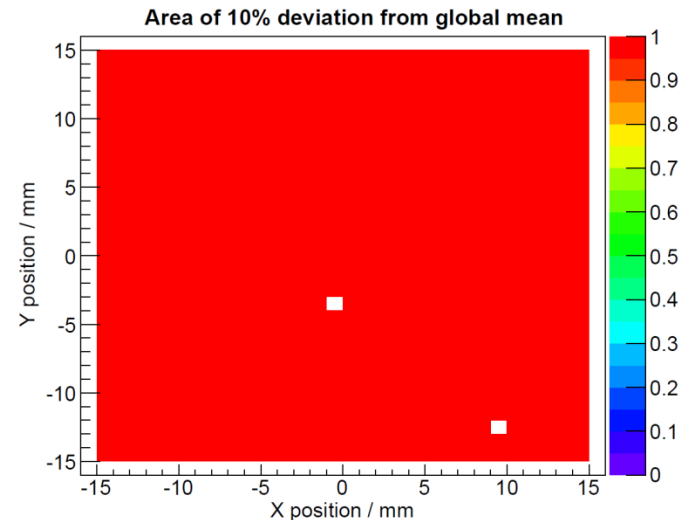
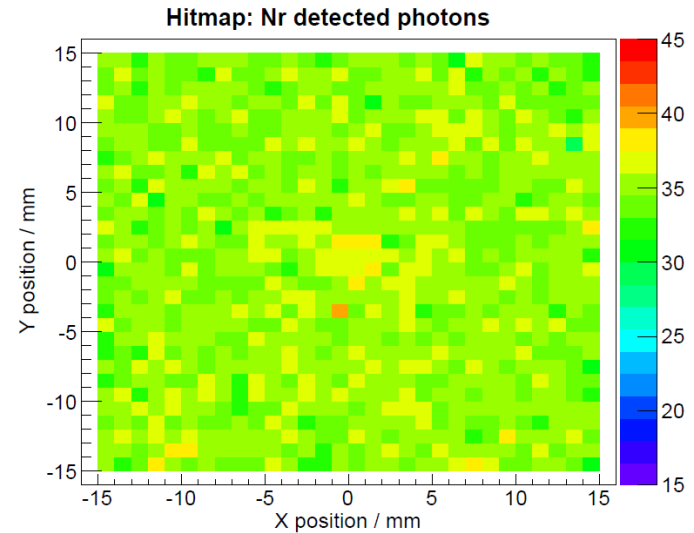
Average: 37.3 detected photons
10% deviation from average: 87.7 % area

Simulations: cone-like dimple (1)

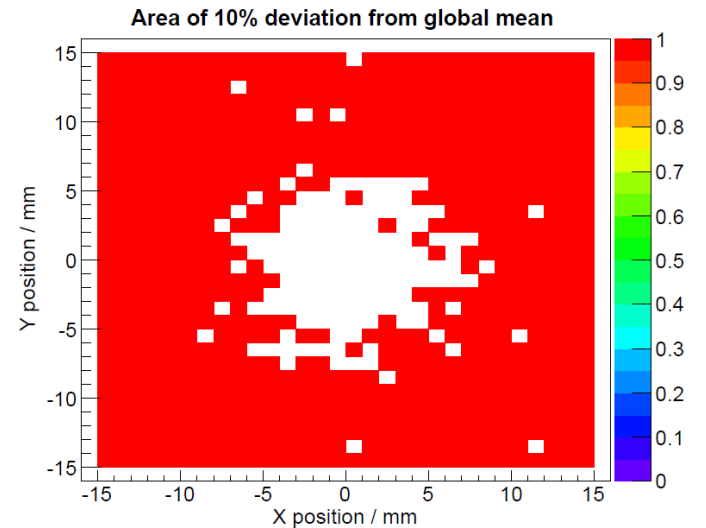
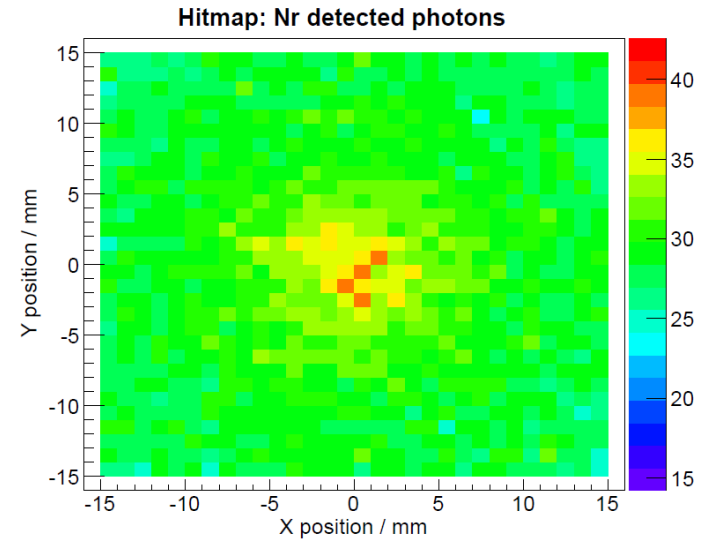
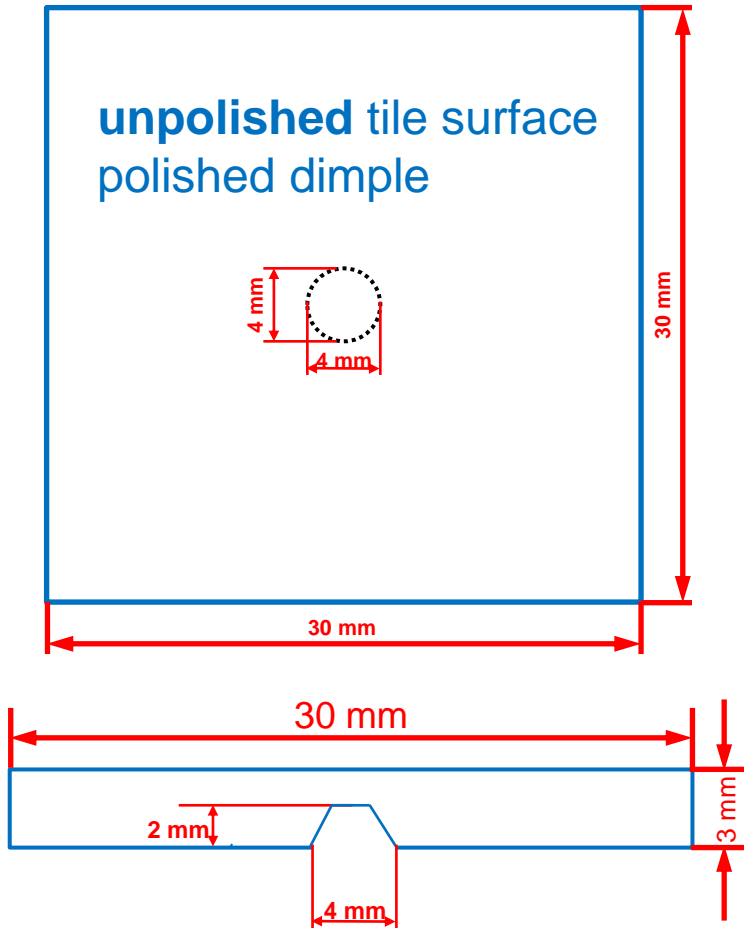


Different dimple shape if it is polished

Average: 34.7 detected photons
10% deviation from average: 99.7 % area



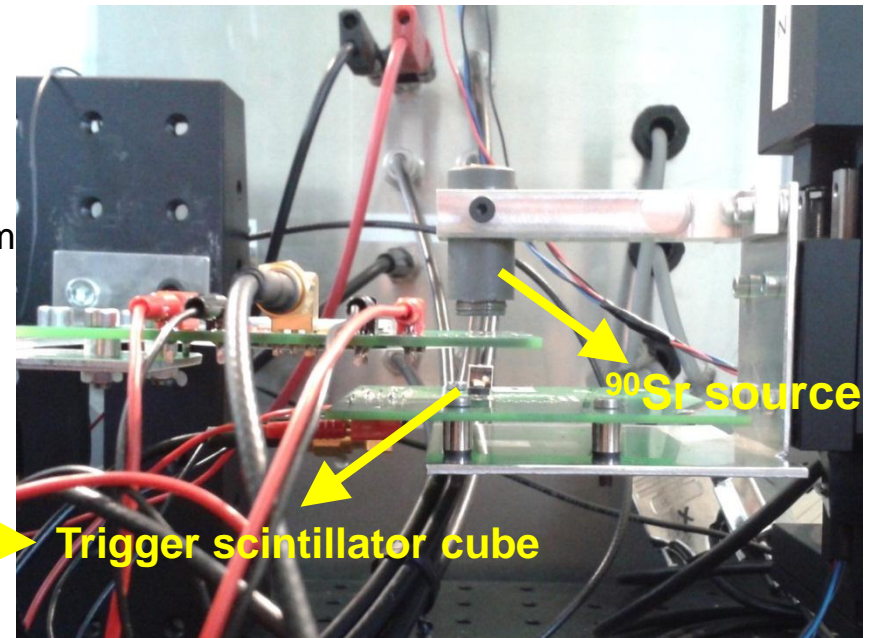
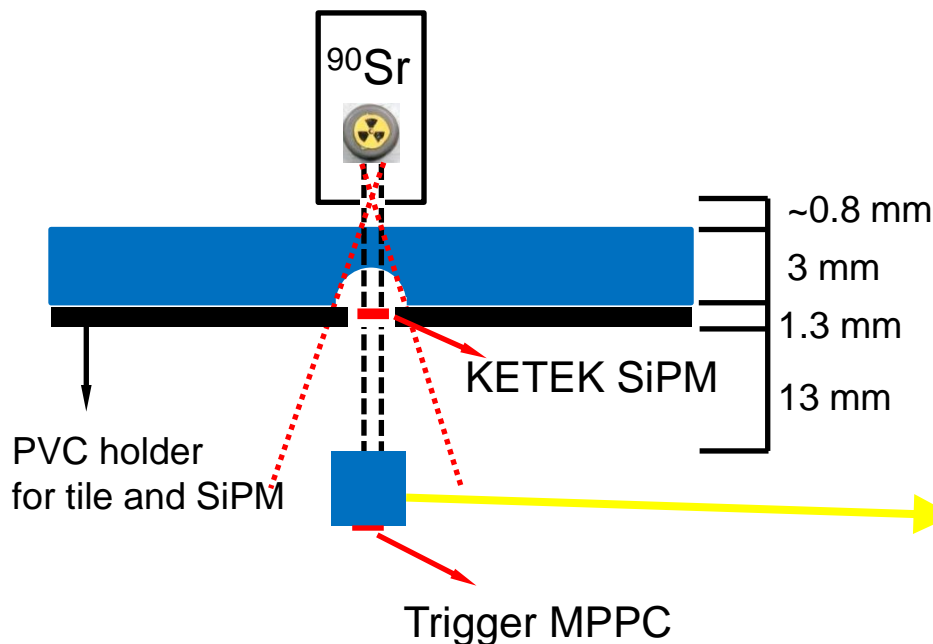
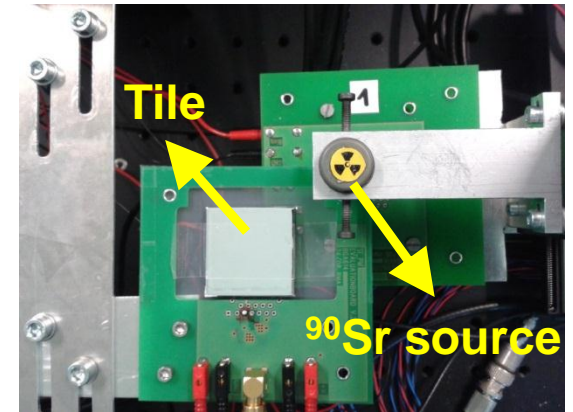
Simulations: cone-like polished dimple (2)



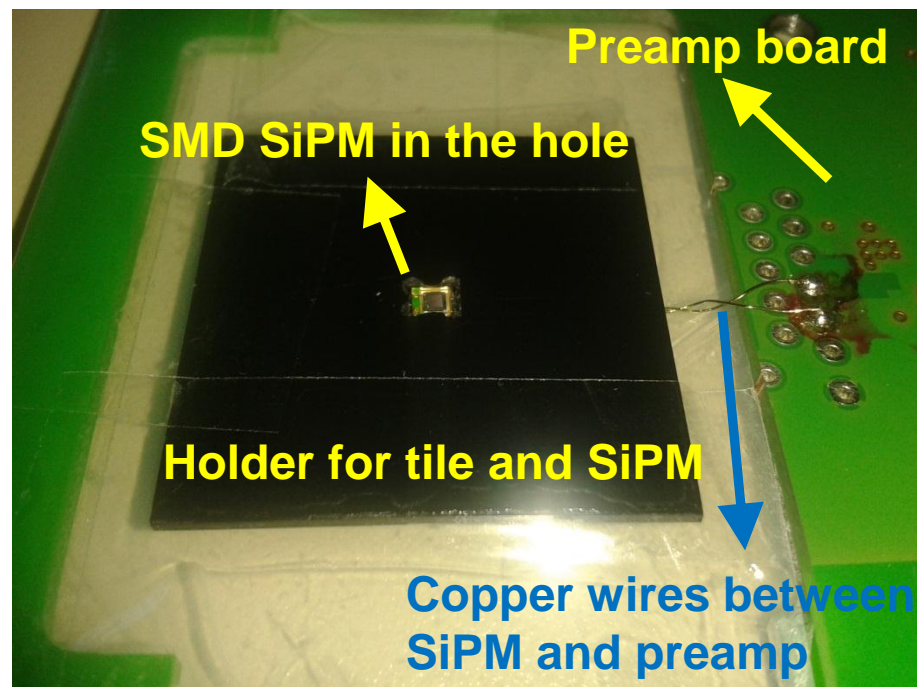
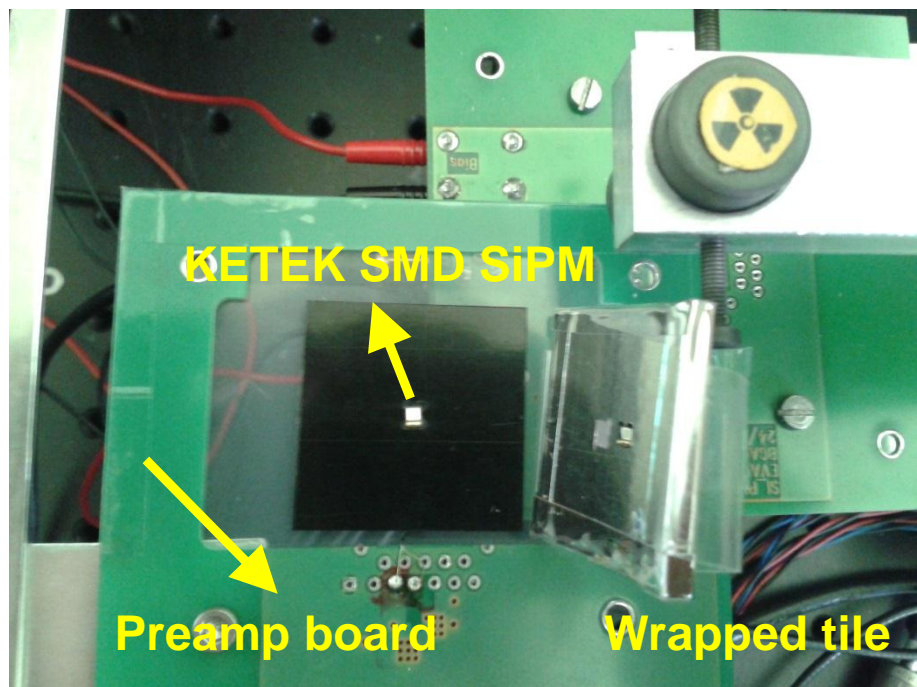
Average: 28.4 detected photons
10% deviation from average: 89.3 % area

Uniformity Measurements in MPI, Munich

- Test setup (Aug, 2013)
 - Strontium 90 source
 - Air-coupled with KETEK SiPM
 - Glue-coupled with 3M foil (DESY)



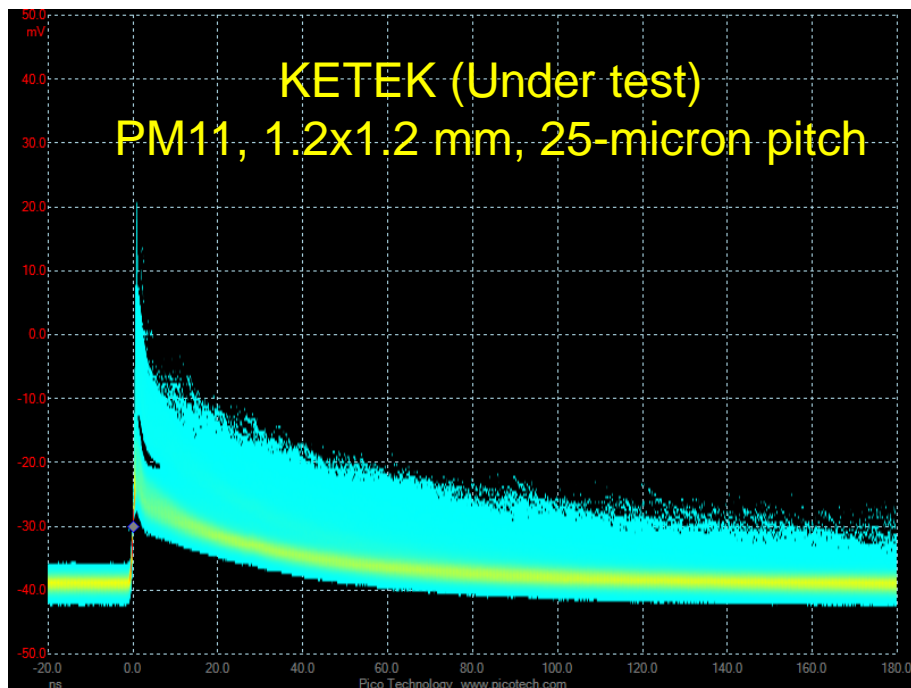
Wrapped tile and its mechanical support



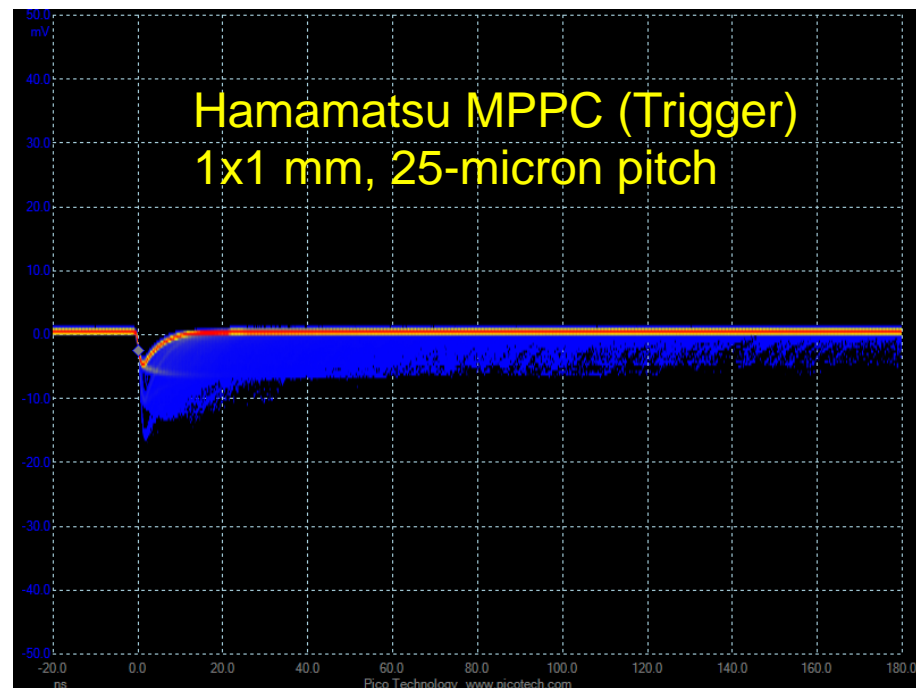
Note: it is difficult to make sure that **SMD SiPM surface** is **horizontal** and to evaluate its **tilted angle**.

This effect may cause an influence on uniformity scan later on.

Single p.e. pulses: KETEK and Hamamatsu



Single p.e. pulse height: ~16 mV
Recovery time: ~100 ns
Threshold: 0.5 p.e.
Operational voltage: 32.4 V



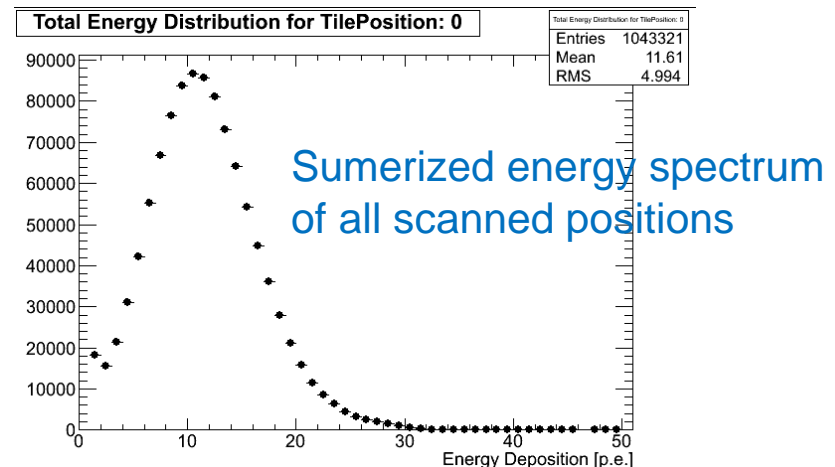
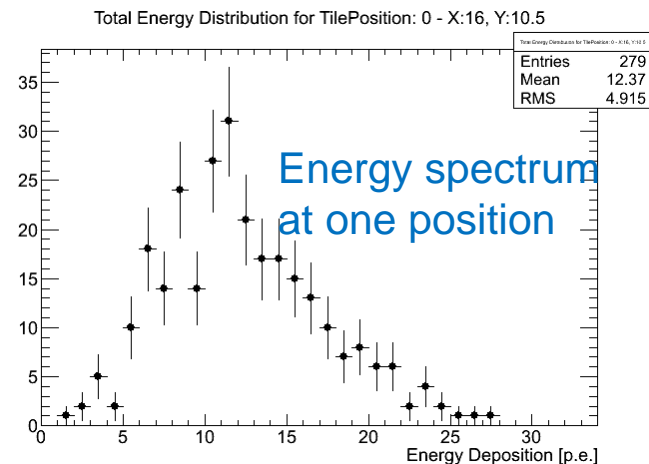
Single p.e. pulse height: ~5 mV
Recovery time: ~10 ns
Threshold: 0.5 p.e.
Operational voltage: ~71 V

Run status

- Operations
 - KETEK SiPM: 32.4 V (20% overvoltage)
 - Trigger SiPM: threshold 7.5 p.e.
 - Time window for data taking: 640 ns
- Data taking (scan step size 0.5 mm)
 - 6 runs of full scanning
 - 3 shapes of dimples
 - 2 types of scintillator tile surfaces
 - polished, unpolished

Data analysis

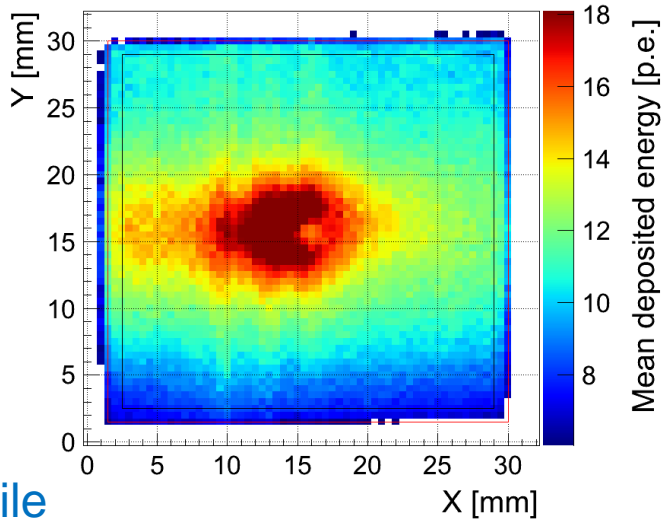
- Time window cut: 9.6ns
 - SiPM after-pulse free
 - Similar technique to T3B analysis
- Energy spectrum (detected p.e.)
 - Get mean value of energy deposition at each position
 - Fill this mean into 2D histogram



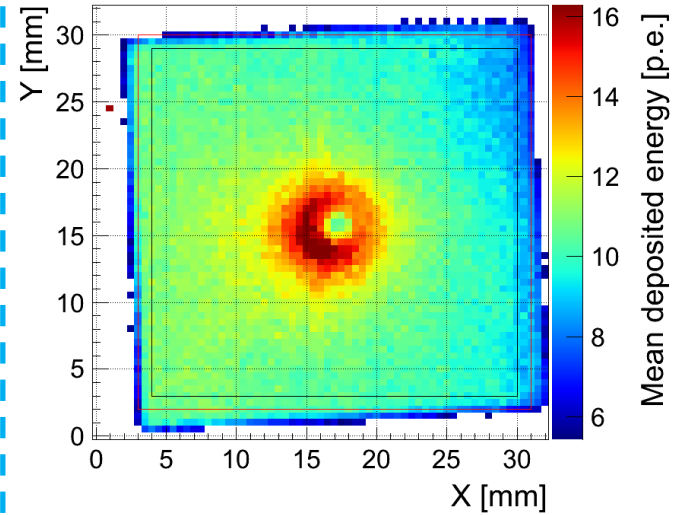
Polished dimple



Plots drawn in MPI T3B analysis framework

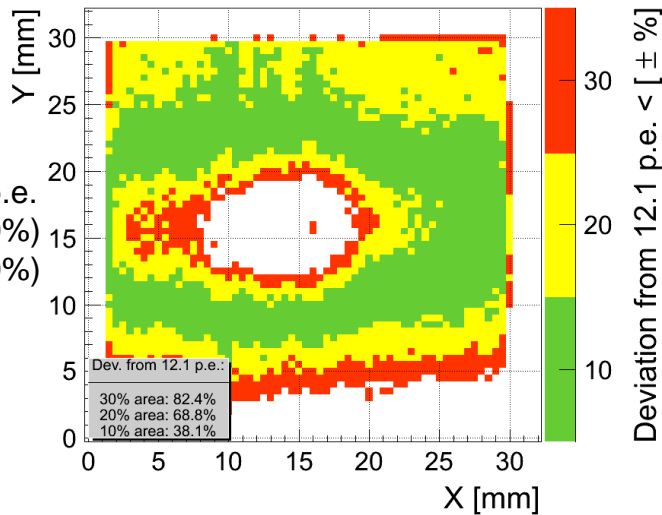


Polished tile surface



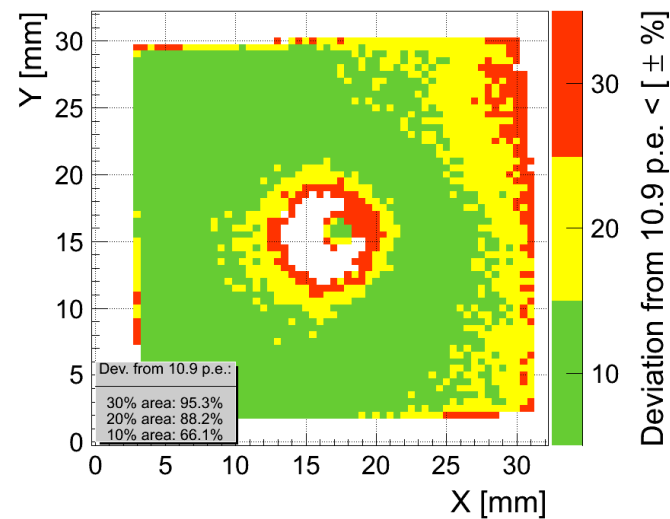
Unpolished surface

Dev. From 12 p.e.
68.8% area (20%)
38.1% area (10%)



Deviation from 12.1 p.e. < [± %]

Dev. from 11 p.e.
88.8% area (20%)
66.1% area (10%)

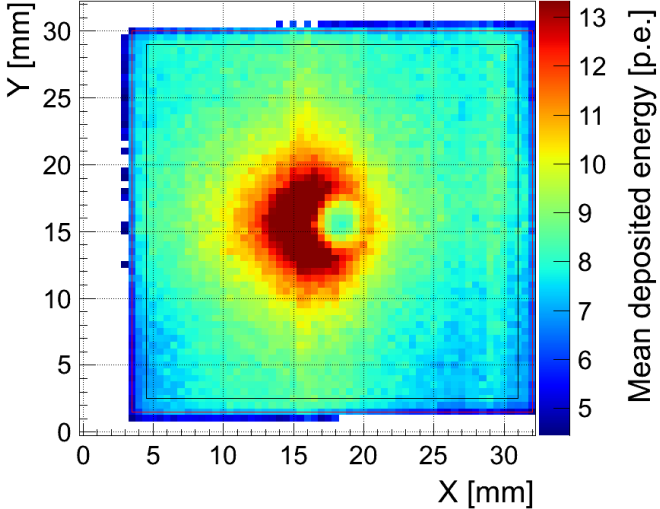
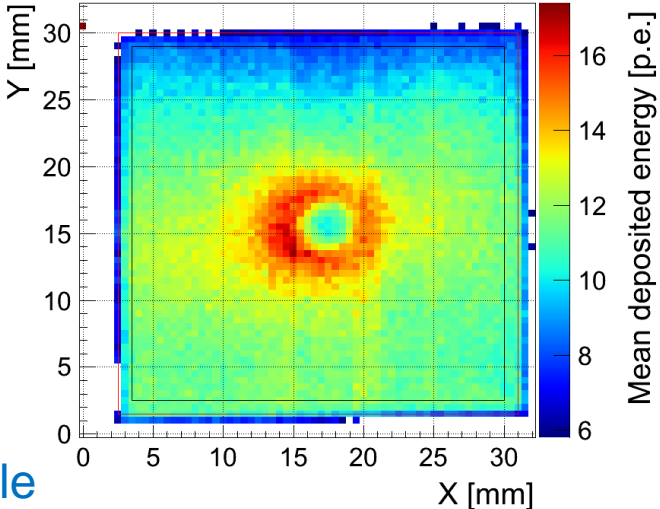


Deviation from 10.9 p.e. < [± %]

Unpolished dimple



Plots drawn in MPI T3B analysis framework

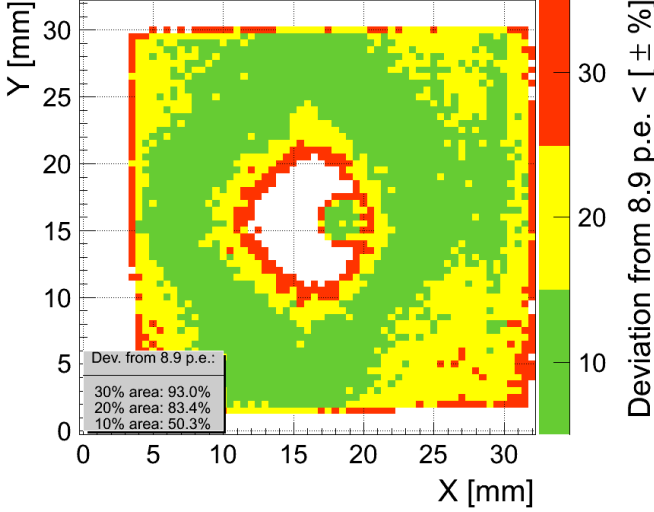
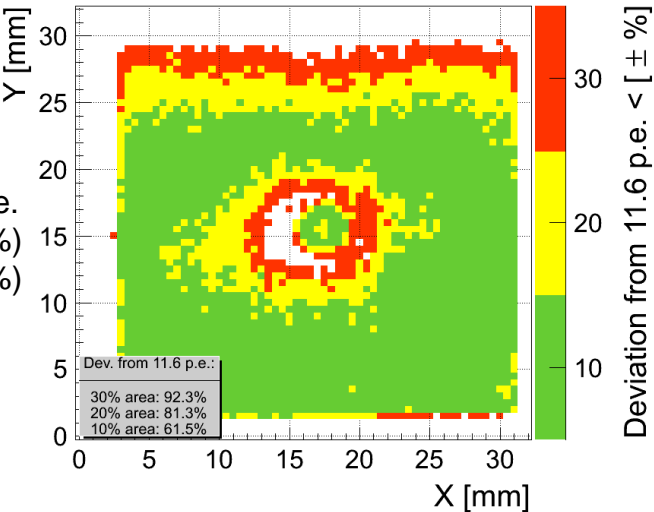


Polished tile surface

Unpolished surface

Dev. From 12 p.e.
81.3% area (20%)
61.5% area (10%)

Dev. from 9 p.e.
83.4% area (20%)
50.3% area (10%)



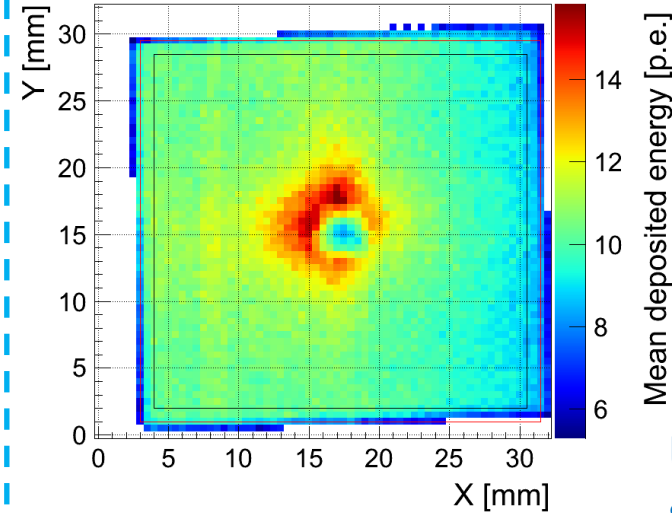
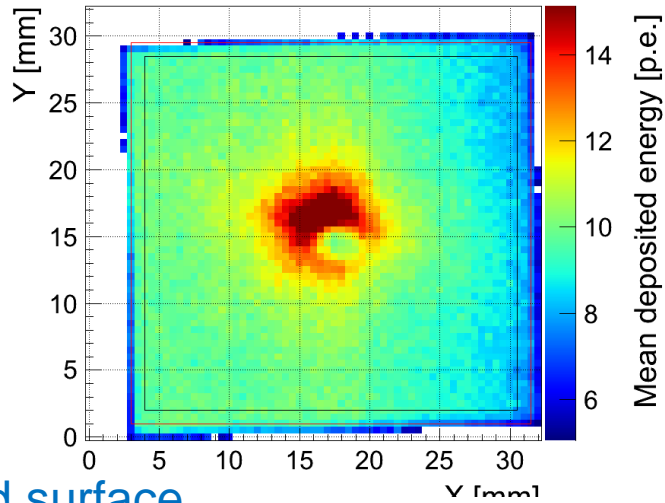
Unpolished dimple



Dome height: 0.5mm;
box depth: 1.0 mm

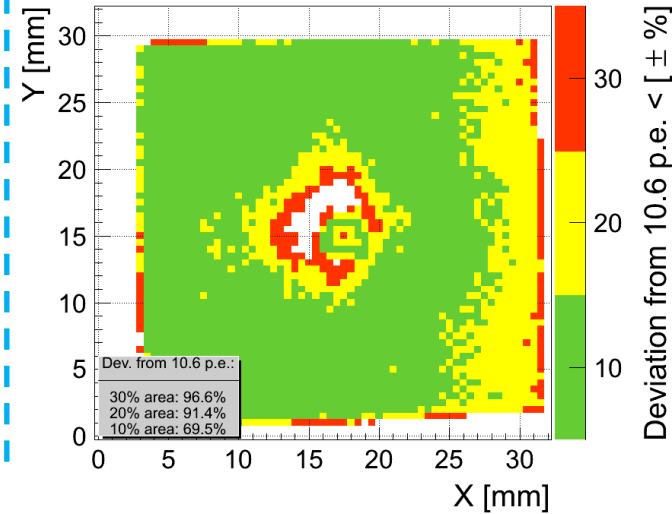
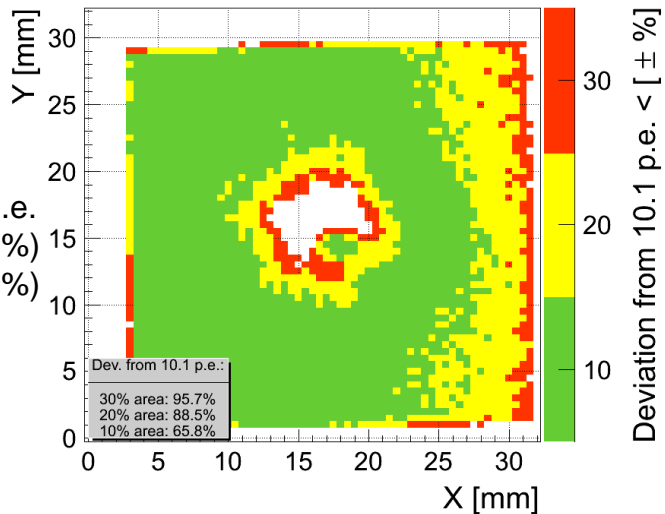
Plots drawn in MPI T3B analysis framework

Dome height: 0.5mm;
box depth: 1.5 mm



Unpolished surface

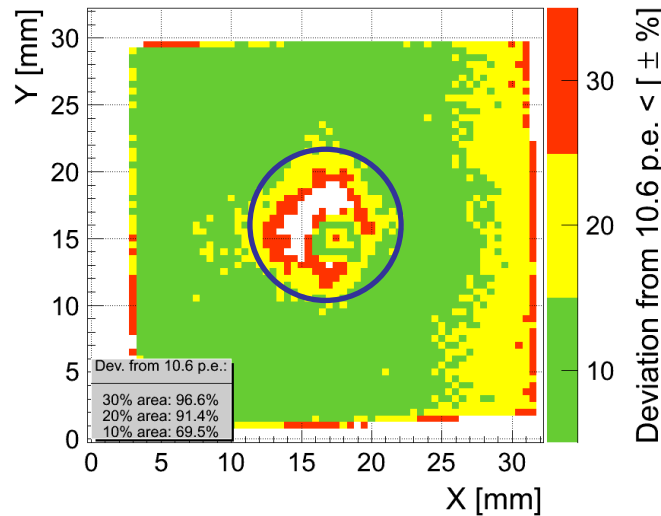
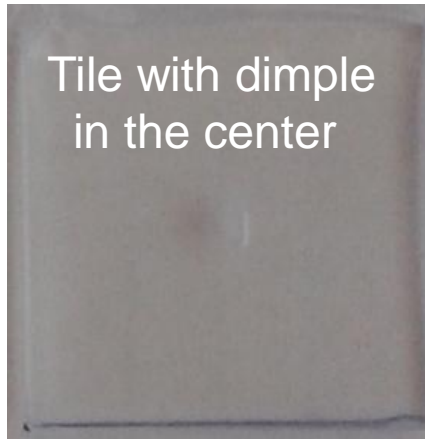
Unpolished surface



Dev. from 11 p.e.
91.4% area (20%)
69.5% area (10%)

Dev. From 10 p.e.
88.5% area (20%)
65.8% area (10%)

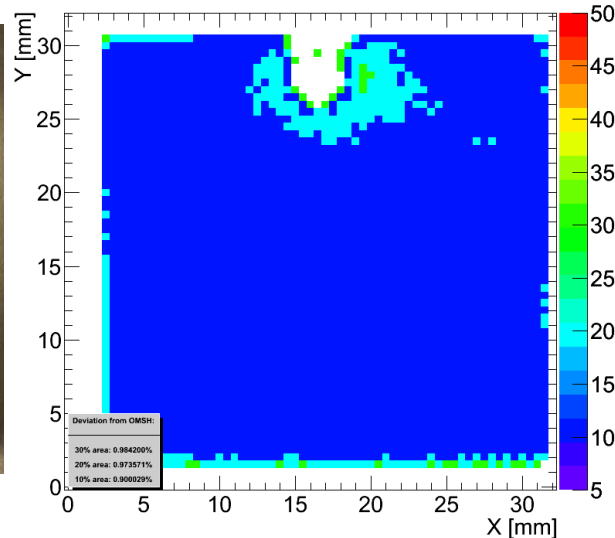
Comparison with uniformity of DESY tile



Overall mean: 11 p.e.

Deviation from mean	Tile area within this deviation
30 %	96.6 %
20 %	91.4 %
10 %	69.5 %

Non-uniformity introduced by dimple in circle is **~14%** of tile Area. Area within 10% dev. would be **~86%**, close to the standard tile



Overall mean signal height: 28.4 p.e.

Deviation from OMSH	Tile area within this deviation
30 %	98.4 %
20 %	97.4 %
10 %	90 %

Ref: First results from ITEP Molded Tiles with Dimple, Christian Soldner, CALICE Collab. Meeting, Shinshu, 2012

Summary

- Simulation
 - Tiles coupled with SMD SiPM
 - Polished tiles suggest better uniformity and more p.e.s
- Uniformity measurements
 - Tiles with different dimples and surface treatment
 - ~86% of tile area can be within 10% deviation from average, if only non-uniformity from dimple area is taken into account
- Simulation and measurements are not well consistent now
 - More detected photons and better uniformity in MC

Outlook

- Uniformity measurements
 - Figure out better way to fix SMD SiPM
 - Horizontal sensitive surface, with no tilting
 - Precise center-positioned
 - Promising if shape is optimized further
 - ~86% of tile area within 10% dev. can be foreseen
- Simulation
 - Energy cut in spectrum of ^{90}Sr source
 - Make sure electrons can pass through entire tile
 - Produce higher statistics of MC samples
 - Suppress statistical fluctuations
 - Optical boundary model for tile surface and foil

Thank you!
Especially thanks to
Frank Simon, Christian Soldner and
Michal Tesař in MPI Munich for
their great help!

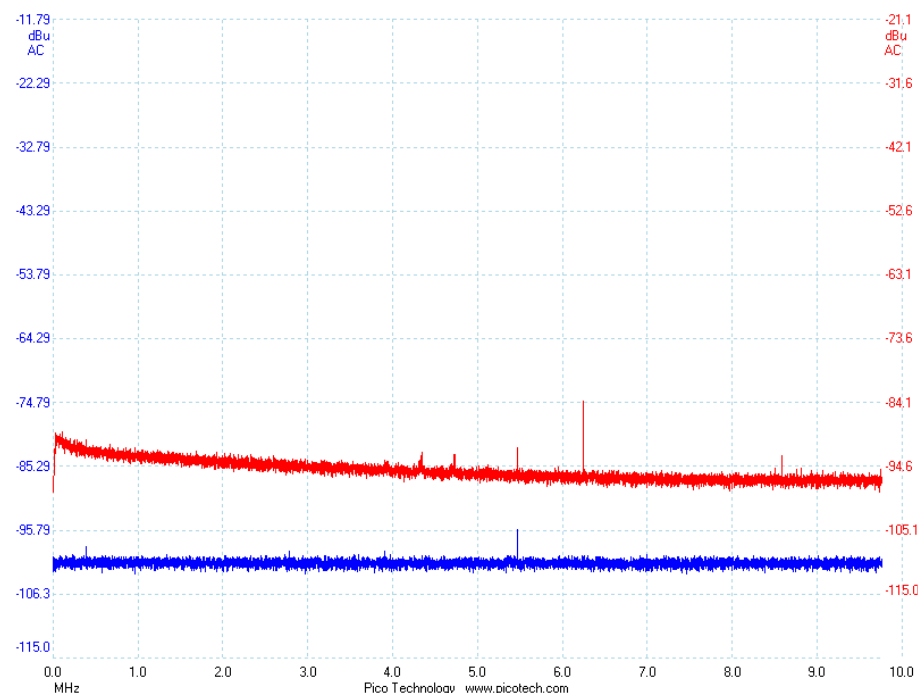
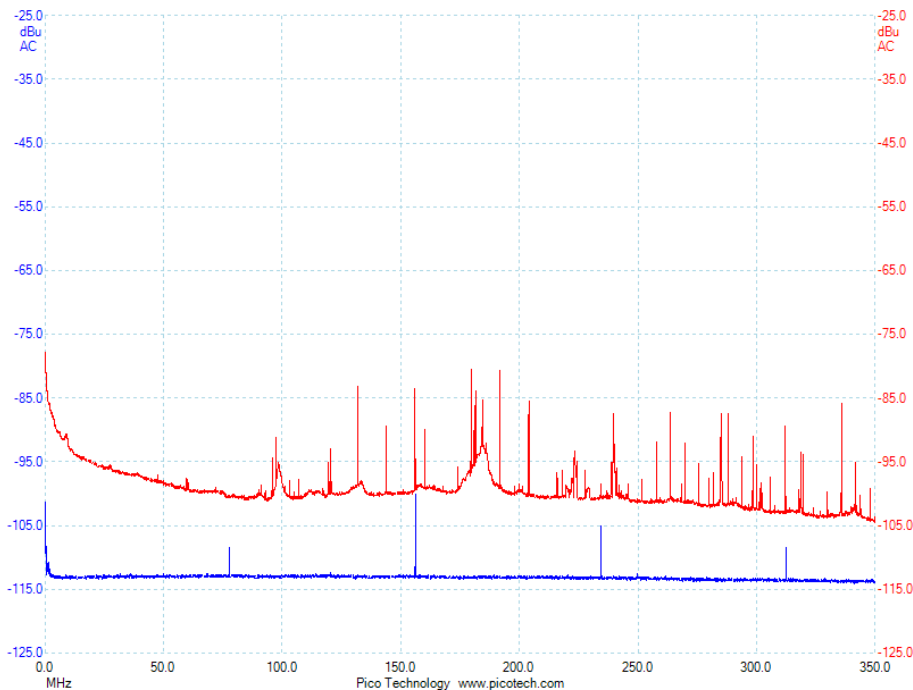
Backup



SiPM noise: frequency spectra

Red: KETEK SMD SiPM PM11

Blue: Trigger SiPM (Hamamatsu MPPC, pinned)

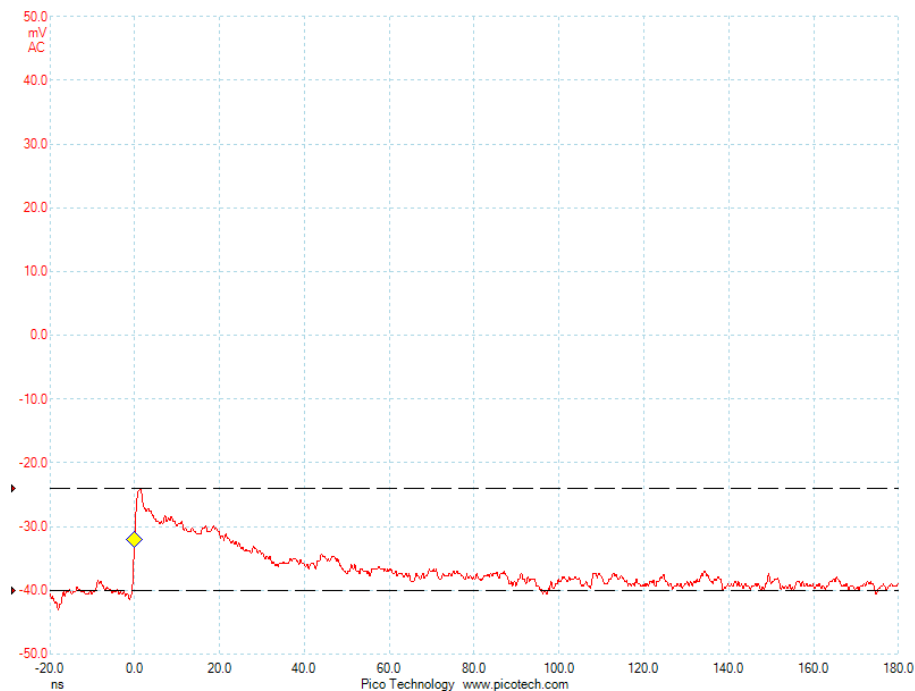


KETEK SiPM soldered with ~5 cm wires: pick up noises at different frequencies

KETEK SiPM soldered with ~1.5 cm Twisted wires: no spike noise observed

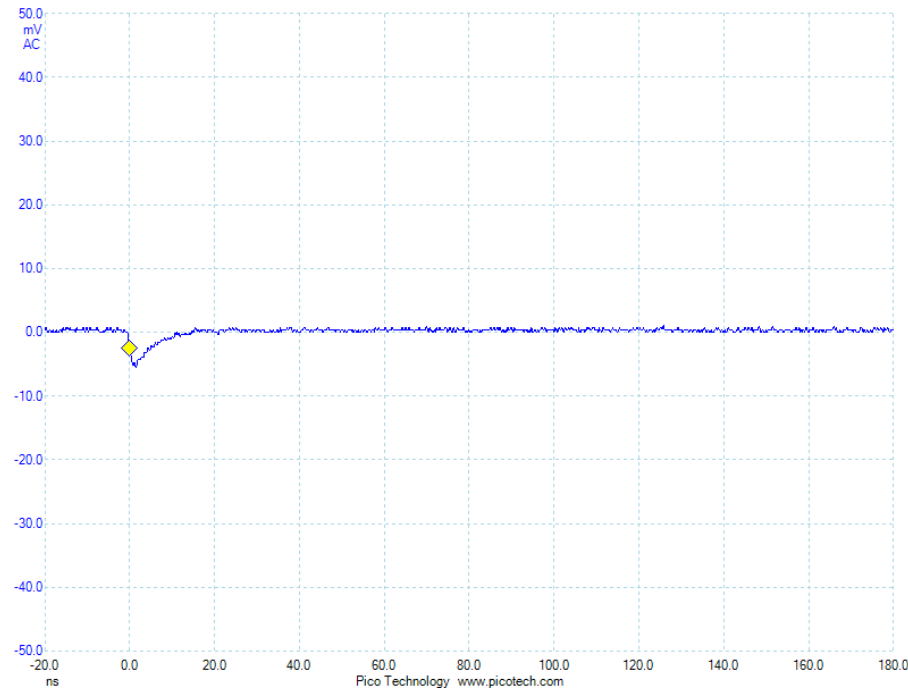
Single p.e. pulses: KETEK and Hamamatsu

KETEK (Under test)



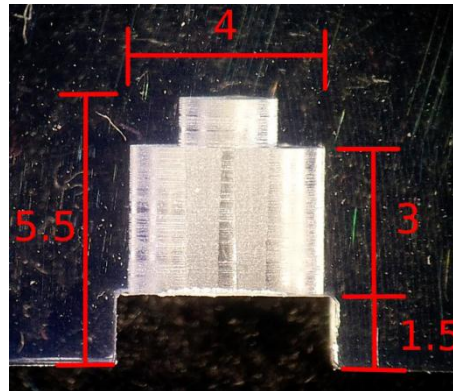
Single p.e. pulse height: ~16 mV
Recovery time: ~100 ns
Threshold: 0.5 p.e.
Operational voltage: 32.4 V

Hamamatsu (Trigger)

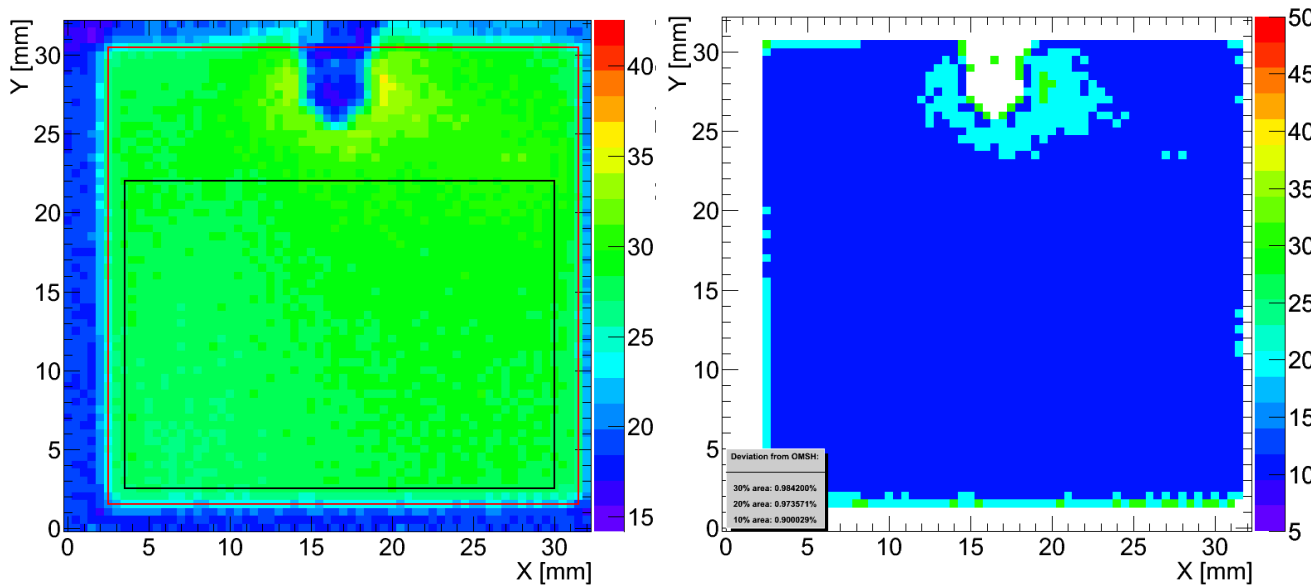
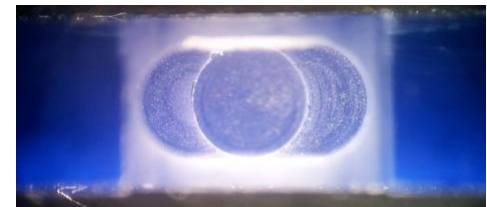


Single p.e. pulse height: ~5 mV
Recovery time: ~10 ns
Threshold: 0.5 p.e.
Operational voltage: 21.7 V

Uniformity of DESY tile with special dimple



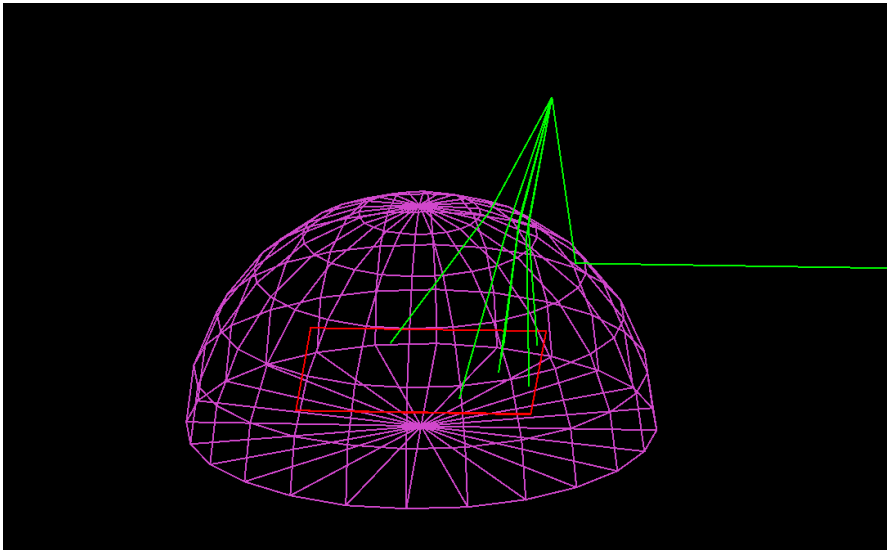
First results from ITEP Molded Tiles with Dimple, Christian Soldner, CALICE Collab. Meeting, Shinshu, 2012



Overall mean signal height: 28.4 p.e.

Deviation from OMSH	Tile area within this deviation
30 %	98.4 %
20 %	97.4 %
10 %	90 %

Optical photons at hemisphere dimple in G4

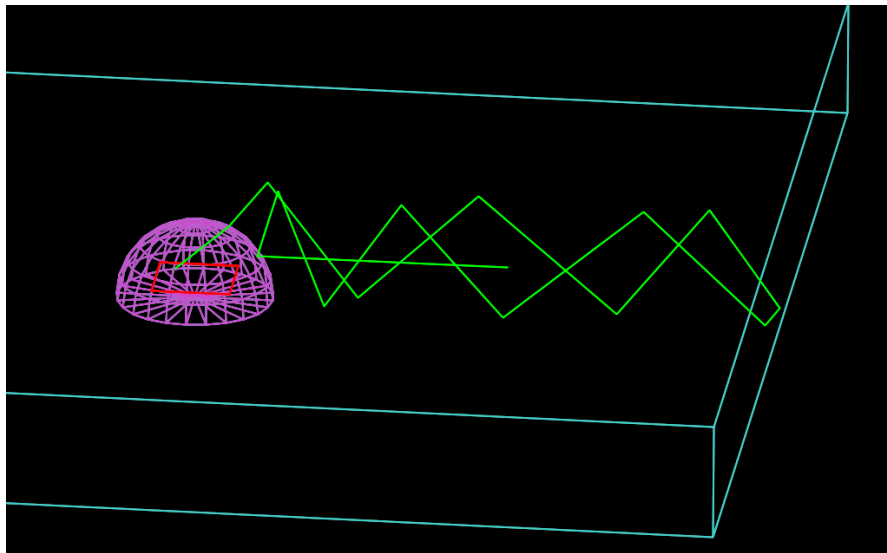


Scintillator tile: 30x30x3 mm³
Dimple in the center of bottom surface

Starting position and momentum direction of optical photons

$$x = 8\text{mm}, y = 0\text{mm}, z = 0\text{mm}$$
$$\theta = 90^\circ, \varphi = 180^\circ$$

Optical surface:
etched tile air coupled with ESR



$$x = 8\text{mm}, y = 0\text{mm}, z = -0.3\text{mm}$$
$$\theta = 90^\circ, \varphi = 180^\circ$$

Critical angle of total reflection at dimple

$$\theta_c = \arcsin\left(\frac{1}{1.58}\right) = 39.3^\circ$$